

Sheet 1 of 2

FORM PTO-1449

INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)

823.0052USQ1

Application Number

09/836,449

Applicant

Fonash et al.

Filing Date

April 17, 2001

Group Art Unit

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## U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
RB	6,288,390	9/11/01	Siuzdak et al.	250	288	

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

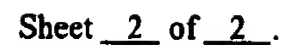
## OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.)

RB	Kim et al. "Thin-Film Micromirror Array." <i>Information Display</i> 4 & 5/99, 30-33.
	Yonehara et al. "ELTRAN; SOI-Epi Wafer by Epitaxial Layer Transfer from Poulos Si." ELTRAN Business Center, Canon, Inc., Abstract No. 438.
	Stern et al. "Nanochannel fabrication for chemical sensors." <i>J. Vac. Sci. Technol.</i> 15(6), Nov/Dec 1997, 2887-2891.
	Turner et al. "Monolithic Fabrication of Nanofluidic Artificial Gel Media for DNA Electrophoresis." <i>SPIE</i> Vol. 3258, 114-121.
	French. "Development of surface micromachining techniques compatible with on-chip electronics." <i>J. Micromech. Microeng.</i> (1996) 197-211.
	Sugiyama et al. "Micromachined sensors using polysilicon sacrificial layer etching technology." <i>IEDM Tech. Dig.</i> , (1994) 127-130.
	Bell et al. "Porous silicon as a sacrificial material." <i>J. Micromech. Microeng.</i> 6 (1996) 361-369.
	Steiner et al. "Using porous silicon as a sacrificial layer." <i>J. Micromech. Microeng.</i> 3 (1993) 32-36.
	Boer et al. "Micromachining of buried micro channels in silicon." <i>J. Micromech. Systems</i> , Vol. 9, No. 1, March 2000, 94-103.
RB	Uhler, Jr. "Electrolytic shaping of Germanium and Silicon." <i>The Bell System Technical Journal</i> . March 1956. 333-347.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP §609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.



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